公益財団法人名古屋産業振興公社　工業技術振興部産業応用課　実績(国際会議)

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計53件　53

＜令和元年度＞　2件　2

K. Takeda, S. Shimizu, S. Takashima, M. Hiramatsu, M. Hori
″Investigation of emission spectrum profile of hydrogen atom in micro-hollow cathode discharge″
24th International Symposium on Plasma Chemistry(ISPC24), P2-21, Naples Conference Center Terminal, Naples, Italy, June 9-14, 2019.

S. Ichimura, S. Takashima, I. Tsuru, D. Ohkubo, H. Matsuo, M. Goto
″Surface analysis of plasma nitrided specimen by STEM-EELS”
AMTC6(The 6th International Symposium on Advanced Microscopy and Theoretical Calculations.)
Castle Plaza Hotel, Nagoya, Japan, June 14-15, 2019

＜平成30年度＞　6件　6

N. Mitsuishi, E. Miura-Fujiwara, M. Yamada1, M. Ito, T. Chiba, H. Sato, M. Nakai, T. Akahori, S. Takashima, Y. Watanabe, M. Niinomi, T. Takeuchi, ″White oxide coating of β Ti-alloy orthodontic wire by atmospheric-pressure plasma treatment″
15th International Symposium on Functionally Graded Materials(ISFGMs2018), P-25, Kitakyushu International Conference Center, Fukuoka, Japan, Aug. 5-8, 2018.

K. Katsuno, T. Tsutsumi, K. Ishikawa, K. Takeda, T. Jindo, S. Takikawa, A. Niwa, S. Takashima, Y. Nonoyama, H. Hashizume, H. Tanaka, H. Kondo, M. Sekine, M. Hori
″Effects of electrical and spectroscopic properties of nonequilibrium atmospheric pressure plasma source on adhesion strengths of a polymeric resin″
40th International Symposium on Dry Process (DPS2018), P-96, Nagoya University, Nagoya, Japan, Nov. 13-15, 2018.

S. Takashima, S. Ichimura, H. Yamamoto, K. Yamakawa, S. Den, M. Iwata, K. Ishikawa, M. Hori
″Cubic boron nitride film deposition by electron beam excited plasma″
11th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2019)/12th International Conference on Plasma-Nano Technology & Science, 18P1-31, Nagoya Institute of Technology, Nagoya, Japan, Mar. 17-21, 2019.

N. Mitsuishi, E. Miura-Fujiwara, M. Yamada, T. Chiba, H. Sato, Y. Watanabe, M. Ito, S. Takashima, M. Nakai, T. Akahori, M. Tanaka, M. Niinomi, T. Takeuchi
″Application of Atmospheric-Pressure Plasma Treatment to Coat Ti-Alloy Orthodontic Wire with White Oxide Layer″
11th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2019)/12th International Conference on Plasma-Nano Technology & Science, 18P1-05, Nagoya Institute of Technology, Nagoya, Japan, Mar. 17-21, 2019.

Susumu Ichimura, Seigo Takashima, Ippei Tsuru, Daichi Ohkubo, Hideaki Matsuo and Mineo Goto
″Nitriding Treatment using Active Screen Plasma and Its Evaluation″
11th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2019)/12th International Conference on Plasma-Nano Technology & Science, 18P1-13, Nagoya Institute of Technology, Nagoya, Japan, Mar. 17-21, 2019.

Riteshkumar Vishwakarma, Zhu Rucheng, Mabuchi Youta, Amr Abuelwafa, Susumu Ichimura, Sudip Adhikari and Masayashi Umeno
″Direct Synthesis of Graphene on Glass by Low Temperature Microwave Plasma Enhanced Chemical Vapor Deposition″
11th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2019)/12th International Conference on Plasma-Nano Technology & Science, 19P4-27, Nagoya Institute of Technology, Nagoya, Japan, Mar. 17-21, 2019.

＜平成29年度＞　1件　1

Eri Miura-Fujiwara, Shimpei Matsutake, Yuu Suzuki, Michiko Ito, Motoko Yamada, Seigo Takashima, Hisashi Sato and Yoshimi Watanabe ″Oxidation of Ti-Nb-Ta-Zr Alloy by Atmospheric Pressure Plasma Treatment″
Biomaterials International 2017, No. 1143, Fukuoka Convention Center, Fukuoka, Japan, Aug. 20 -24, 2017.

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＜平成28年度＞　6件　6

K. Yamaguchi, M. Ito, S. Takashima, M. Kitahara, S. Nakata, T. Okadera, H. Asano
″Analyses of Aqueous Dispersions of TiO2 Nanoparticles Prepared by Using Plasma on Liquid Surface″
9th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2017)/10th International Conference on Plasma-Nano Technology & Science, 04P77, Chubu University, Nagoya, Japan, Mar. 1-5, 2017.

Y. Suzuki, M. Yamada, Y. Watanabe, H. Sato, E. Miura-Fujiwara, M. Ito, S. Takashima
″Effects of Shot Peening and Atmospheric Pressure Plasma on Aesthetic Improvement of Ti Alloy for Dental Applications″
9th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2017)/10th International Conference on Plasma-Nano Technology & Science, 03P31, Chubu University, Nagoya, Japan, Mar. 1-5, 2017.

Y.Nonoyama, M.Ito, S.Takashima, A.Niwa, A.Higashida, K.Yanagihara, T.Ikedo, T.Jindo, K.Takeda, K.Ishikawa, M.Hori
″Influence of polypropylene due to excessive irradiation of atmospheric pressure plasma″
9th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2017)/10th International Conference on Plasma-Nano Technology & Science, 03P75, Chubu University, Nagoya, Japan, Mar. 1-5, 2017.

S. Takashima, M. Ito, H. Asano, M. Kitahara, S. Nakata, K. Yamaguchi
Aqueous dispersion of TiO2 nanoparticles obtained by the plasma on liquid surface and its dispersion mechanism″
19th Interfinish World Congress (INTERFINISH2016), ID175, China National Convention Center, Beijing, China, Sep. 20-22, 2016.

S. Takashima, Y. Nonoyama, M. Hayakawa, K. Yanagihara, T. Hamane, T. Ikedo, T. Jindo, K Takeda, K. Ishikawa, M. Hori
″Temperature Effect of Atmosphere Pressure Plasma for Adhesive Strength of Polypropylene-resin″
19th Interfinish World Congress (INTERFINISH2016), ID174, China National Convention Center, Beijing, China, Sep. 20-22, 2016.

H. Hara, K. Oshima, H. Tanaka, A. Horie, T. Suzuki, . Matsushita, S. Takashima, M. Kume
″Development of copper plated polymer fiber conductor″
19th Interfinish World Congress (INTERFINISH2016), ID86, China National Convention Center, Beijing, China, Sep. 20-22, 2016.

＜平成27年度＞　5件　5

Y.Nonoyama, M.Hayakawa, S.Takashima, K.Yanagihara, T.Hamane, T.Ikedo, T.Jindo, K.Takeda, K.Ishikawa, M.Hori
″Temperature Effect of Oxygen Radical Density on Atmosphere Pressure Plasma″
8th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2016)/9th International Conference on Plasma-Nano Technology & Science, 08aB03O, Nagoya University, Nagoya, Japan, Mar. 6-10, 2016.

Sho Takitou, Michiko Ito, Seigo Takashima, Norio Nomura, Tominori Kitagawa and Hirotaka Toyoda
″Development of High-Throughput Liquid Treatment System using Slot Antenna Excited Microwave Plasma″
68th Gaseous Electronics Conference / 9th International Conference on Reactive Plasmas / 33rd Symposium on Plasma Processing, LW00092, Hawaii Convention Center, Honolulu, Hawaii, Oct, 12-16, 2015

Michiko Ito, Seigo Takashima, Norio Nomura, Tominori Kitagawa and Hirotaka Toyoda
″Organic Decomposition Performance of In-line Liquid Treatment System Using Microwave Plasma″
68th Gaseous Electronics Conference / 9th International Conference on Reactive Plasmas / 33rd Symposium on Plasma Processing, LW00093, Hawaii Convention Center, Honolulu, Hawaii, Oct, 12-16, 2015

Michiko Ito, Seigo Takashima, Norio Nomura, Tominori Kitagawa and Hirotaka Toyoda
″Optimization of In-line Plasma Treatment Performance″
10th Asian-European International Conference on Plasma Surface Engineering, 22P1-41, Ramada Plaza Jeju Hotel, Jeju Island, Korea, Sep. 20-24, 2015.

S. Den, H. Yamamoto, K. Yamakawa, M. Hayakawa, E. Asami, S. Takashima, H. Wada, M. Hori
″Plasma Nitriding Process for Aluminium Alloy of Al-Mg″
10th Asian-European International Conference on Plasma Surface Engineering, 23P3-31, Ramada Plaza Jeju Hotel, Jeju Island, Korea, Sep. 20-24, 2015.

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＜平成26年度＞　2件　2

M. Ito, S. Takashima, N. Nomura, T. Kitagawa, H. Toyoda
″Influence of Solution Temperature on Processing Performance by In-line Plasma Treatment Device″
7th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2015)/8th International Conference on Plasma-Nano Technology & Science, A6-P-22, Nagoya University, Nagoya, Japan, Mar. 26-31, 2015.

M. Ito, S. Takashima, N. Nomura, T. Kitagawa, H. Toyoda
″DEVELOPMENT OF IN-LINE PLASMA TREATMENT DEVICE FOR MEDICINE″
2nd International Workshop on Plasma for Cancer Treatment, P-36, Nagoya University, Nagoya, Japan, Mar. 16-17, 2015.

＜平成25年度＞　1件　1

M. Ito, T. Takahashi, S. Takashima, N. Nomura, T. Kitagawa, H. Toyoda
″Decomposition of Phenol by Pulsed Microwave Plasma Generated in the Vicinity of a Fluid Flow Path″
6th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2014)/7th International Conference on Plasma-Nano Technology & Science, 03pP-16, Meijo University, Nagoya, Japan, Mar. 2-6, 2014.

＜平成24年度＞①　11件　11

S. Takashima, M. Ito, M. Hayakawa, H. Yamamoto, K. Yamakawa, S. Den
″Plasma nitriding for aluminium alloy of Al-Mg″
5th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2013), P4018A, Nagoya University, Nagoya, Japan, Jan. 28 - Feb. 1, 2013.

M. Ito, S. Takashima, E. Asami, T. Aoki, M. Oka, H. Asano, M. Kitahara, S. Nakata, K. Yamaguchi, Y. Murase
″Properties of aqueous dispersions of TiO2 nanoparticles prepared by plasma on liquid surface: Effect of the multiplication of the plasma″
5th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2013), P4034C, Nagoya University, Nagoya, Japan, Jan. 28 - Feb. 1, 2013.

M. Hayakawa, M. Ito, S. Takashima, H. Matsuo, M. Goto
″Hardening of SACM645 steel using a pulsed discharge atmospheric pressure plasma nitriding″
5th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2013), P2035A, Nagoya University, Nagoya, Japan, Jan. 28 - Feb. 1, 2013.

K. Yamakawa, H. Yamamoto, S. Takahashi, S. Den, S. Takashima, M. Hori
″Rapid and low-temperature nitridation of austenitic stainless steel using electron beam excited plasma (EBEP)″
5th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2013), P2092C, Nagoya University, Nagoya, Japan, Jan. 28 - Feb. 1, 2013.

S. Takashima, M. Ito, M. Hayakawa, E. Asami and M. Kume
″Adhesion enhancement of electroless Copper plating on Aramid fiber treated by radical processing with atmospheric pressure plasma″　Interfinish2012, S08G-01, Politecnico di Milano, Milano, Italy, Nov. 14-16, 2012

M. Ito, M. Hayakawa, S. Takashima, E. Asami, T. Aoki, M. Oka, H. Asano, M. Kitahara, S. Nakata, K. Yamaguchi and Y. Murase
″Application of plasma on liquid surface to disperse titanium dioxide nanoparticles in water″
Interfinish2012, S10-06, Politecnico di Milano, Milano, Italy, Nov. 14-16, 2012

M. Hayakawa, M. Ito, S. Takashima, H. Matsuo, and M. Goto
″Nitriding of Al-Cr-Mo steel using pulsed discharge atmospheric pressure plasma″
Interfinish2012, S14-08, Politecnico di Milano, Milano, Italy, Nov. 14-16, 2012

S. Takashima, M. Ito, M. Hayakawa, E. Asami, M. Kume
″Metal Plating of Aramid Fibers using Radical Processing employing Atmospheric Pressure Plasma”
11th Asia Pacific Conference on Plasma Science and Technology and 25th Symposium on Plasma Science for Materials(11th APCPST and 25th SPSM), 3P-85, Kyoto University, Kyoto, Japan, Oct. 2-5, 2012

S. Den, Y. Higashijima, H. Kano, S. Takashima, M. Hori
″Rapid Nitriding Low Temperature using Electron Beam Excited Plasma”
11th Asia Pacific Conference on Plasma Science and Technology and 25th Symposium on Plasma Science for Materials(11th APCPST and 25th SPSM), TR-18, Kyoto University, Kyoto, Japan, Oct. 2-5, 2012

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＜平成24年度＞②

H. Yokoyama, R. Kawauchi, S. Takashima, M. Hori
″The Development of Device for Atmospheric-Pressure Plasma Evaluation”
11th Asia Pacific Conference on Plasma Science and Technology and 25th Symposium on Plasma Science for Materials(11th APCPST and 25th SPSM), TR-15, Kyoto University, Kyoto, Japan, Oct. 2-5, 2012

M. Hayakawa, S. Takashima
″Effect on adhesion improvement of polar groups on resin materials formed by atmospheric pressure”
11th Asia Pacific Conference on Plasma Science and Technology and 25th Symposium on Plasma Science for Materials(11th APCPST and 25th SPSM), 1P-37, Kyoto University, Kyoto, Japan, Oct. 2-5, 2012

＜平成23年度＞　2件　2

M. Ito, S. Takashima, E. Asami, T. Aoki, M. Oka, H. Asano, M. Kitahara, S. Nakata, K. Yamaguchi and Y. Murase
“Aqueous dispersion of TiO2 nanoparticles prepared by plasma on liquid surface”
4th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2012), P2108C, Chubu University, Kasugai, Aichi, Japan, Mar. 4-8, 2012.

M. Hayakawa, S. Takashima
“Adhesion Improvement of Resin Materials Using Non-equilibrium Atmospheric Pressure Plasma Pretreatment”
4th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2012), P1074C, Chubu University, Kasugai, Aichi, Japan, Mar. 4-8, 2012.

＜平成22年度＞　3件　3

K. Murata, M. Naito, M .Hiramatsu, S. Takashima, H. Kondo and M. Hori
“Determination of C Atom Density in Microwave Plasma with Carbon-Containing Gases by Vacuum Ultraviolet Absorption Spectroscopy”
3rd International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials(ISPlasma2011), Nagoya Institute of Technology, Nagoya, Japan, Mar. 6-9, 2011.

S. Takashima, M. Ito and S. Sawada
“Inner Surface Treatments of Long Polymer Tubes using Tubular Low-Pressure Plasma”
3rd International Symposium on Advanced Plasma Science and its Application for Nitrides and Nanomaterials (ISPlasma2011), P2-070C, Nagoya Institute of Technology, Nagoya, Japan, Mar. 6-9, 2011.

S. Takashima, M. Ito, S. Uchida, T. Aoki and M. Kume
“Hydrophilic Treatment of Inner Surface of Polymer Tubes using Tubular Low-Pressure Plasma”
63rd Gaseous Electronics Conference & 7th International Conference on Reactive Plasmas, CTP102, Maison de la Chimie, Paris, France, Oct. 4-8, 2010.

＜平成21年度＞　3件　3

C.S. Moon, K. Takeda, S. Takashima, M. Sekine, Y. Setsuhara, M. Shiratani and M. Hori
“Surface Loss Probabilities of H, N Radicals in Afterglow Plasma”
The 3rd International Conference on Plasma-Nano Technology & Science (IC-PLANTS2010), P-75, Meijo University, Nagoya Japan, Mar. 11-12, 2010.

S. Chen, H. Kano, S. Den, K. Takeda, S. Takashima, M. Sekine and M. Hori
“Development of high density radical source and the behaviors of radicals in N_2-H_2 mixture plasma”
AVS 56th International Symposium and Exhibition, PS1-WeM11, p.112, San Jose McEnery Convention Center, Nov. 8-13, San Jose, CA, 2009.

Ch. S. Moon, K. Takeda, S. Takashima, M. Sekine, Y. Setsuhara, M. Shiratani and M. Hori
“Investigation of Surface Loss Probabilities of H, N Radicals in Afterglow Discharge employing Vacuum Ultra-Violet Absorption Spectroscopy”
International Conference on Micro and Nano Engineering (MNE2009), P-NANO, p76, ICC Ghent, Ghent, Belgium, Sep. 28 - Oct. 1, 2009.

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＜平成20年度＞　11件 11

S. Chen, H. Kano, S. Den, S. Takashima, K. Takeda and M. Hori
“Development of High Density Nitrogen Radical Source and Behaviors of Atomic Radicals”
1st International Symposium on Advanced Plasma Science and its Applications (ISPlasma2009), Mo-3 (p.134), Nagoya University, Nagoya, Japan, Mar. 8-11, 2009.

Y. Miyawaki, K. Takeda, M. Fukasawa, K. Oshima, K. Nagahata, T. Tatsumi, S. Takashima, M. Sekine and M. Hori
“Damages on Low-k Films due to VUV, UV Radiation, Radical and Ion in Low-k Films Etching Employing H_2/N_2 Plasma”
The 2nd International Conference on Plasma-Nano Technology & Science, P-52, IB Building, Nagoya University, Nagoya, Japan, Jan. 22-23, 2009.

Y. Miyawaki, K. Takeda, S. Takashima, M. Sekine and M. Hori
“Evaluating Damages on Organic Low-k Films due to VUV, UV Radiation, Radical and Ion in Dual Frequency Capacitively Coupled Plasma”
The 8th International Workshop of Advanced Plasma Processing and Diagnostics Joint Workshop with Plasma Application Monodzukuri(PLAM), Techno Plaza, Gifu, Japan, Jan. 20-21, 2009.

S. Takashima, K. Takeda and M. Hori
Sticking Coefficients of Atomic Radicals for Flexible Electronics
The 8th International Workshop of Advanced Plasma Processing and Diagnostics Joint Workshop with Plasma Application Monodzukuri(PLAM), Techno Plaza, Gifu, Japan, Jan. 20-21, 2009.

Chang S. Moon, K. Takeda, T. Hayashi, S. Takashima, M. Sekine, Y. Setsuhara, M. Shiratani and M. Hori
“Surface Loss Rate of H and N Radicals in H_2/N_2 Plasma Etching Process”
61st Annual Gaseous Electronics Conference, DT1 5, p.19, Marriott Dallas/Addison Quorum, Dallas, Texas, USA, October 13-17, 2008.

Y. Miyawaki, K. Takeda, M. Fukasawa, K. Oshima, K. Nagahata, T. Tatsumi, S. Takashima, M. Sekine and M. Hori
“Damages on Organic Low-k Films due to VUV, UV Radiation, Radical and Ion in Dual Frequency Capacitively Coupled Plasma”
2nd Japanese-German Student Workshop on Plasma Science and Technology, Ruhr-University of Bochum, Bochum, Germany, October 12-14, 2008.

Y. Miyawaki, K. Takeda, M. Fukasawa, K. Oshima, K. Nagahata, T. Tatsumi, S. Takashima, M. Sekine and M. Hori
“Damages on Organic Low-k Films due to VUV, UV Radiation, Radical and Ion in Dual Frequency Capacitively Coupled Plasma”
European Summer School ″Low Temperature Plasma Physics: Basics and Applications″, Physikzentrum Bad Honnef, Bad Honnef, Germany, Oct 4-11, 2008.

S. Takashima, R. Saito, S. Uchida, K. Takeda, M. Fukasawa, K. Oshima, K. Nagahata, T. Tatsumi and M. Hori
“Diagnostics of Plasma Induced Damages on Low-k SiOCH Films”
2008 International Conference on Solid State Device and Materials, pp. 716-717, Tsukuba International Congress Center, Tsukuba, Japan, September 23-26, 2008.

T. Ohta, Y. Tachibana, N. Takota, M. Ito, S. Takashima, Y. Higashijima, H. Kano, S. Den and M. Hori
“Simultaneous Monitoring of Absolute Densities of Multi Metallic Atoms in Magnetron Sputtering Employing Micro Hollow Cathode Lamp”
11th International Conference on Plasma Surface Engineering, OR1901, Kongresshaus (Congress Center), Garmisch-Partenkirchen, Germany, September 15-19, 2008.

M. Hori, S. Takashima, S. Takahashi, K. Yamakawa, S. Den, H. Kano, M. Sekine, M. Shiratani and Y. Setsuhara
“Optical Probe for Atomic Radical Monitoring and its Application to Advanced Plasma Nano-processing based on Plasma Science”
1st International Conference on Microelectronics and Plasma Technology, p. 36, Ramada Plaza Jeju Hotel, Jeju, Korea, August 18-20, 2008.

H. Yamamoto, K. Takeda, S. Takashima, M. Sekine and M. Hori
“Quantitative Measuring of Damage on Porous SiOCH by H_2/N_2 Plasma Ashing Process”
17th World INTERFINISH Congress & Exhibition, PC-103 p573, Grand Hotel Haeundae, Busan, Korea, June 16-19, 2008.